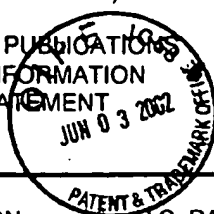


FORM PTO-1449 (MODIFIED)

ATTORNEY DOCKET NO.
SP00-191SERIAL NO.
10/048,138LIST OF PATENTS AND PUBLICATIONS
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DISCLOSURE STATEMENT

APPLICANT Davis et al.

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REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS (CONT'D)

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
IK	A7	5,220,590	6/15/93	Bruning et al.			
	A8	5,315,629	5/24/94	Jewell et al.			
	A9	5,332,702	7/26/94	Sempolinski et al.			
	A10	5,353,322	10/4/94	Bruning et al.			
	A11	5,395,413	3/7/95	Sempolinski et al.			
	A12	5,395,738	3/7/95	Brandes et al.			
	A13	5,553,110	9/3/96	Sentoku et al.			
	A14	5,565,030	10/15/96	Kado et al.			
	A15	5,605,490	2/25/97	Laffey et al.			
	A16	5,686,728	11/11/97	Shafer			
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	A18	5,868,605	2/9/99	Cesna			
	A19	5,970,751	10/26/99	Maxon et al.			
	A20	5,989,776	11/23/99	Felter et al.			
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	A22	6,176,588	1/23/01	Davis, Jr. et al.			
	A23	6,188,150	2/13/01	Spence			
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	A25	6,280,294	8/28/01	Miyamoto			
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IK	A28	Properties of Corning's Glass and Glass Ceramic Families, pp. 1-23, 1979
	A29	P. C. Shultz et al., <i>Ultra-Low-Expansion Glasses and Their Structure in the SiO₂ and TiO₂ System</i> , presented to the Third International Conference on the Physics of Non-crystalline Solids, Sheffield University, September 1970.
	A30	"Industrial Applications of Silica," Beall, G. H., <i>Reviews in Mineralogy</i> , Vol. 29, pages 469-505.
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	A32	"Ultra-low-expansion glasses and their structure in the SiO ₂ -TiO ₂ System," Schultz et al., <i>Amorphous Materials</i> , Sept. 1970, pages 453-461.
	A33	"Extreme Ultraviolet Lithography," Gwyn et al., <i>EUV LLC</i> , Nov. 1999, pages 97-141.
	A34	Tanya E. Jewell, <i>Four-Mirror Ring-Field System for EUV Projection Lithography</i> , 1994, pages 98-102.
	A35	High Purity Quartz Glass Products, 5/17/99, http://www.toshiba-ceramics.com/quartz.html , pages 1-2.
IK	A36	Shin-Etsu Chemical Homepage, Semiconductor Materials Division, 5/17/99, http://www.shinetsu.co.jp/english/profile/division/sem-div/sem-div.html , pages 1-2.

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Sakel Kishore

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APPLICANT Davis et al.

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REFERENCE DESIGNATION PATENT & TRADEMARK OFFICE PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
IK	AA	09/943,466	8/30/01	Ackerman et al.			
	AB	09/943,445	8/30/01	Bowden et al.			
	AC	09/943,252	8/30/01	Best et al.			
	AD	09/676,721	9/28/00	Yu			
	AE	09/506,162	2/17/00	Hrdina et al.			
	AF	2001/0028462	10/11/01	Ichihara et al.			
	AG	2,272,342	2/10/42	Hyde			
	AH	2,326,059	8/3/43	Nordberg			
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	AR	5,043,002	8/27/91	Dobbins et al.			
	AS	5,076,700	12/31/91	DeCaprio			
	AT	5,146,518	9/8/92	Mak et al.			
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IK	AV	5,154,744	10/13/92	Blackwell et al.			

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		Document Number	Date	Country	Class	Sub-Class	Translation Yes	No
IK	AW	WO 00/48952 /	8/24/00	PCT				
	AX	WO 00/03400 /	1/20/00	PCT				
	AY	WO 01/75522 /	10/11/01	PCT				
	AZ	WO 01/08163 /	2/1/01	PCT				
	A1	WO 01/07967 /	2/1/01	PCT				
	A2	1 106 582A2 /	6/13/01	EPC				
IK	A3	0 349 925A1 /	1/10/90	EPC				

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IK	A4		Rapid Prototyping (11/5/01); http://mtiac.iitri.org/pubs/rp/rp1.htm
IK	A5		3D Systems: Leftnav (11/5/01); http://www.3dsystems.com/products/slssystems/vanguard/index.asp?promo=
I	A6		ULE: Zero Expansion Glass (10/31/01); http://www.corning.com/semiconductormaterials/products_services/ule.asp

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	APPLICANT Davis et al.	
	FILING DATE 1/22/02	GROUP TO BE ASSIGNED TBA

OTHER INFORMATION (Including Author, Title, Date, Pertinent Pages, etc.) (CONT'D)

JK	A37	✓	Isimoto Co., Ltd., Products for Optics, 5/17/99, http://www.isimoto.ocm/isimoto/english/variation3.html , pages 1-2.
	A38	✓	Isimoto Co., Ltd., Product Information, 5/17/99, http://www.isimoto.ocm/isimoto/english/product_info.html , pages 1-4.
	A39	✓	Isimoto Co., Ltd., Purity and Chemical Reactivity, 5/17/99, http://www.isimoto.ocm/isimoto/english/feature1.html , pages 1-3.
	A40		The Optics Mail – Equipment/Supplies, Universal Photonics, Inc., 7/7/99, page 1.
	A41	✓	Rodel Authored Papers: A Study of the Variation of Physical Properties in Random Lots of Urethane Polishing Pads for CMP, 7/7/99, http://www.rodel.com/publications/paper1.asp , pages 1-4.
	A42		Rodel Publications Content, Rodel Authored Papers, 7/7/99, http://www.rodel.com/publications/content.asp , pages 1-2.
	A43		Rodel Publications, 7/7/99, http://www.rodel.com/publications/default.asp , page 1.
	A44	✓	Cab-O-Sil Web Site, 7/7/99, http://www.cabot-corp.com/cabosil , pages 1-3.
	A45	✓	Optics and Photonics News, August 1999, Vol. 10, No. 8, August 1999, pages 34-38.
	A46		Gianoulakis et al., <i>Thermal management of EUV lithography masks using low expansion glass substrates</i> , Proceedings of the SPIE – The International Society for Optical Engineering (1999), vol. 3676, pt. 1-2, p. 598-605.
	A47	✓	O.V. Mazurin, V. K. Leko and L.A. Komarova, Journal of Non-Crystalline Solids 18 (1975) 1-9, Crystallization of Silica and Titanium Oxide-Silica Corning Glasses (Codes 7940 and 7971), pages 1-9.
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	A49	✓	H. E. Hagy and W. D. Shirkey, Determining absolute thermal expansion of titanica-silica glasses: a refined ultrasonic method, September 1975, Vol. 14, No. 9, Applied Optics, pages 2099-2103.
	A50	✓	S. F. Jacobs et al., Surface figure changes due to thermal cycling hysteresis, Applied Optics, Vol. 26, No. 20, October 15, 1987, pages 4438-4442
	A51	✓	C.W. Gwyn, R. Stulen, D. Sweeney and D. Attwood, Extreme Ultraviolet Lithography, pages 1-9 and 1-6.
	A52	✓	Richard H. Stulen and Donald W. Sweeney, Extreme Ultraviolet Lithography, IEEE Journal of Quantum Electronics, Vol. 35, No. 5, May 1999, pages 694-699
	A53	✓	William M. Tong, John S. Taylor, Stephen P. Vernon, Substrates Requirements For Extreme Ultraviolet Lithography, Lawrence Livermore National Laboratory.
JK	A54	✓	EUV Lithography NGL Technology Review, June 9, 1999.

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